Diethoxymethylsilane (DEMS®) is used as a silicon source for the chemical vapor deposition of high quality low dielectric constant films and silicon dioxide films. When used in the PDEMS® ILD process, it can be used to deposit ultra low-k films with k ≤2.5 and below.

**STANDARD PACKAGE INFORMATION—ASIA, NORTH AMERICA & EUROPE**

<table>
<thead>
<tr>
<th>Material Number</th>
<th>438217</th>
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</thead>
<tbody>
<tr>
<td>Container</td>
<td>38L Stainless Steel</td>
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<tr>
<td>Fill Weight (grams)</td>
<td>31,400</td>
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<tr>
<td>Level Sensor</td>
<td>None</td>
</tr>
<tr>
<td>Valve Type</td>
<td>Pneumatic Quick Connect SL Diaphragm</td>
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<tr>
<td>Inlet Valve Connection</td>
<td>¼” Male VCR</td>
</tr>
<tr>
<td>Outlet Valve Connection</td>
<td>¾” Female VCR Diptube</td>
</tr>
<tr>
<td>Backfill Gas</td>
<td>Helium</td>
</tr>
<tr>
<td>Delivery Method</td>
<td>DLI</td>
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</table>

**PHYSICAL CHARACTERISTICS**

<table>
<thead>
<tr>
<th>Formula</th>
<th>C₅H₁₄O₂Si</th>
<th>Density</th>
<th>0.830g/mL @ 20°C</th>
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</thead>
<tbody>
<tr>
<td>Molecular Weight</td>
<td>134.3</td>
<td>Boiling Point</td>
<td>~95°C</td>
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<tr>
<td>Flash Point</td>
<td>10°C</td>
<td>Vapor Density (air=1)</td>
<td>7.5</td>
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<tr>
<td>Freezing Point</td>
<td>&lt;0°C</td>
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**RELATED PRODUCTS**

a-Terpinene (ATRP) is used as a porogen source for the chemical vapor deposition of high quality low dielectric constant films. When used in the DEMS® ILD process, it can be used to deposit ultra low-k films with k ≤2.5 and below.

CHEMGUARD® Automated Chemical Refill System—dual reservoir cabinet designed to continuously supply chemical to the process tool

Stainless steel containers feature EXTREMA® Finish, a proprietary micropolish technique designed to prevent rust, discoloration and weld slag

CHEMGUARD-BCD (Bulk Chemical Delivery) is a 220 liter capacity chemical delivery system. The BCD features 316L stainless steel piping and a large flow capacity suitable for the requirements of high-volume fabwide chemical supply.
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